In the Claims:

A listing of the claims remaining in the application follows including amendments to claims 1 and 18, and the addition of new claims 55-58:

1. (currently amended): A reduced glare, conductive coated panel comprising:

a transparent substrate having a first surface and a second surface;

a first, multilayer stack disposed on said first surface of said substrate, said first stack comprising at least a first transparent, thin film layer, a second transparent, thin film layer and a third transparent, thin film layer;

a second, multilayer stack disposed on said second surface of said substrate, said second stack comprising at least a first transparent, thin film layer, a second transparent, thin film layer and a third transparent, thin film layer;

each thin film layer in said first stack having a corresponding thin film layer in said second stack;

each of said transparent, thin film layers of said first stack being a wet chemical formed thin film layer and having a refractive index, said first transparent, thin film layer of said first stack being disposed on said first surface of said substrate, said second transparent, thin film layer of said first stack being disposed on said first thin film layer of said first stack, and said third transparent, thin film layer of said first stack being disposed on said second thin film layer of said first stack;

each transparent, thin film layer of said second stack being a wet chemical formed thin film layer and having the refractive index of its corresponding transparent, thin film layer of said first stack; said first transparent, thin film layer of said second stack being disposed on said second surface of said substrate, said second transparent, thin film layer of said second stack being disposed on said first thin film layer of said second stack, and said third transparent, thin film layer of said second stack being disposed on said second thin film layer of said second stack;

the film thickness of any one of said thin film layers of said second stack being different than the thickness of its corresponding thin film layer of said first stack;

at least one of said thin film layers of said first stack having a thickness greater than the thickness of its corresponding thin film layer of said second stack;

the material composition of said corresponding layers in each of said first and second stacks being the same; the refractive index of each of said second thin film layers in said first and second stacks being greater than the refractive index of the other thin film layers in said first and second stacks; the refractive index of said third thin film layer in each of said first and second stacks being less than the refractive index of the other thin film layers in said first and second stacks;

a transparent conductive thin film on said third thin film layer of said first stack, said transparent conductive thin film being a vacuum deposited thin film and comprising a material selected from at least one of indium tin oxide, doped tin oxide, and doped zinc oxide; and

whereby visible light transmission through said coated panel is increased as compared to said substrate coated only with said transparent conductive thin film.

2. (original): The coated panel of claim 1 wherein said transparent substrate is glass.

3. (original): The coated panel of claim 1 wherein said transparent substrate is selected from the group consisting of glass and plastic.

4.-7. (canceled)

8. (previously presented): The coated panel of claim 1 wherein said first layers in each of said first and second stacks are formed from a combination of silicon dioxide and titanium dioxide, each of said first layers having a refractive index at the sodium D line in the range of from about 1.5 to about 2.0.

9. (previously presented): The coated panel of claim 1 wherein said second layers in each of said first and second stacks are formed from titanium dioxide, said second layers each having a refractive index at the sodium D line of at least about 2.0.

10. (previously presented): The coated panel of claim 1 wherein said third layers in each of said first and second stacks are formed from silicon dioxide, said third layers each having a refractive index at the sodium D line of less than about 1.5.

11.-14. (canceled)

15. (previously presented): The coated panel of claim 1 wherein said second stack comprises a transparent conductive thin film on said third thin film layer of said second stack, said transparent conductive thin film on said second stack being selected from at least one of indium tin oxide, doped tin oxide, and doped zinc oxide.

16 (canceled)

17. (original): The coated panel of claim 1 wherein each of said layers of said first stack has a thickness greater than the thickness of said corresponding layer of said second stack on said second surface.

18. (currently amended): A reduced glare, conductive coated panel comprising:

a transparent substrate having a first surface and a second surface;

a first, transparent, interference thin film disposed on said first surface of said substrate;

a second, transparent, interference thin film disposed on said second surface of said substrate;

said first thin film corresponding to but having a thickness greater than said second thin film;

a third thin film disposed on said first thin film and a fourth thin film disposed on said second thin film, said third thin film corresponding to but having a thickness greater than said fourth thin film;

a fifth thin film disposed on said third thin film and a sixth thin film disposed on said fourth thin film, said fifth thin film corresponding to but having a thickness greater than said sixth thin film;

the material composition of each of said corresponding thin films being the same; and

a transparent conductive coating on said fifth thin film, said transparent conductive coating being a vacuum deposited coating and selected from at least one of indium tin oxide, doped tin oxide, and doped zinc oxide;

each of said first, second, third, fourth, fifth and sixth thin films being a wet chemical formed thin film and having a refractive index, the refractive index of said third and fourth thin films being greater than the refractive index of the other thin films, said refractive index of the fifth and sixth thin films being less than the refractive index of the other thin films; and

whereby visible light transmission through said coated panel is increased compared to said substrate coated only with said transparent conductive coating.

19.-24. (canceled)

25. (previously presented): The coated panel of claim 18 also including said transparent conductive coating on said sixth thin film.

26.-33. (canceled)

34. (withdrawn) A method for making a reduced glare, conductive coated panel comprising:

providing a transparent substrate having a first surface and a second surface;

forming a first transparent thin film layer on said first surface and a first transparent thin film layer on said second surface by dipping said substrate in a liquid solution of a precursor of a material for said first transparent thin film layers while maintaining said substrate at an angle to the vertical whereby said first layer on said first surface has a thickness greater than the thickness of said first layer on said second surface; and

applying a layer of a transparent electrically conductive coating over at least one of said first layer on said first surface and said first layer on said second surface.

35. (withdrawn) The method of claim 34 including firing said dipped substrate at an elevated temperature to complete transformation of said as-dipped layers into said transparent

thin films prior to said applying said layer of transparent electrically conducting coating in order.

36. (withdrawn) The method of claim 34 wherein said angle is between about 5 and 25 degrees.

37. (withdrawn) The method of claim 34 including forming a second transparent thin film layer on said first layer on said first surface and a second transparent thin film layer on said first layer on said second surface by dipping said substrate in a liquid solution of a precursor of a material for said second transparent thin film layers while maintaining said substrate coated with said first said second transparent thin film layer on at least one of said first surface and said second surface subsequent to forming said second transparent thin film layer on said first layer on said first surface and said second transparent thin film layer on said first layer on said second surface.

38. (withdrawn) The method of claim 37 wherein said angle for dipping said coated substrate to form said second layers is between about 5 and 25 degrees.

39. (withdrawn) The method of claim 37 including applying a transparent electrically conductive coating over each of said second layer on said first surface and said second layer on said second surface.

40. (withdrawn) The method of claim 34 including forming a third transparent thin film layer on said second layer on said first surface, and a third transparent thin film layer on said second layer on said second surface by dipping said substrate in a liquid solution of a precursor of a material for said third transparent thin film layers while maintaining said substrate coated with said first and second layers at an angle to the vertical, and applying said transparent electrically conductive coating to said third transparent thin film layer on at least one of said first surface and said second surface subsequent to forming said third transparent thin film layer on said second layer on said first surface and said second layer on said second surface.

41. (withdrawn) The method of claim 40 wherein said angle for dipping said coated substrate to form said third layers is between about 5 and 25 degrees.

42. (withdrawn) The method of claim 40 including applying a transparent electrically conductive coating over each of said third layer on said first surface and said third layer on said second surface.

43. (withdrawn) The method of claim 42 including applying said transparent electrically conductive coating by vacuum deposition.

44. (withdrawn) The method of claim 43 wherein said vacuum deposition comprises sputtering.

45. (withdrawn) The method of claim 40 including applying said transparent electrically conductive coating by vacuum deposition.

46. (withdrawn) The method of claim 45 wherein said vacuum deposition comprises sputtering.

47. (withdrawn) The method of claim 34 including applying a transparent electrically conductive coating over each of said first layer on said first surface and said first layer on said second surface.

48. (withdrawn) The method of claim 34 including applying said transparent electrically conductive coating by vacuum deposition.

49. (withdrawn) The method of claim 48 wherein said vacuum deposition comprises sputtering.

50. (withdrawn) The method of claim 34 wherein said dipping said substrate in the liquid solution includes withdrawing said substrate from the liquid solution in a direction parallel to the direction in which said substrate extends when maintained at said angle to the vertical.

51.-52. (canceled)

53. (previously presented): The coated panel of claim 8 wherein said second layers in each of said first and second stacks are formed from titanium dioxide, said second layers each having a refractive index at the sodium D line of at least about 2.0.

54. (previously presented): The coated panel of claim 53 wherein said third layers in each of said first and second stacks are formed from silicon dioxide, said third layers each having a refractive index at the sodium D line of less than about 1.5.

55. (new): The coated panel of claim 1 wherein said wet chemical formed thin film layers comprise angle dipped thin film layers wherein said substrate is dipped into a liquid solution of a precursor of the respective first, second or third thin film layers while maintaining said substrate at a predetermined angle to the vertical to simultaneously coat each of said first and second surfaces of said substrate or the previous thin film layers on said first and second surfaces of said substrate, following which said coated layers are cured with at least one of ultraviolet light, air drying and heating/firing.

56. (new): The coated panel of claim 55 wherein said vacuum deposited thin film comprises a sputtered thin film.

57. (new): The coated panel of claim 18 wherein said wet chemical formed thin films comprise angle dipped thin films wherein said substrate is dipped into a liquid solution of a precursor of the respective first and second, or third and fourth, or fifth and sixth thin films while maintaining said substrate at a predetermined angle to the vertical to simultaneously coat each of said first and second surfaces of said substrate or the previous thin films on said

first and second surfaces of said substrate, following which said coated layers are cured with at least one of ultraviolet light, air drying and heating/firing.

58. (new): The coated panel of claim 57 wherein said vacuum deposited coating comprises a sputtered coating.